1. Record Nr. UNINA9910452174403321

Autore	Citron Stephen
Titolo	Jerry Herman [[electronic resource]] : poet of the showtune / / Stephen Citron
Pubbl/distr/stampa	New Haven, : Yale University Press, c2004
ISBN	1-281-73143-9 9786611731434 0-300-13324-3
Descrizione fisica	1 online resource (1 online resource (xiii, 338 p.)) : ill
Disciplina	782.1/4/092 B
Soggetti	Composers - United States Electronic books.
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	"Songs, shows, music in print, and recordings": p. .
Nota di bibliografia	Includes bibliographical references (p. 313-314) and index.
Nota di contenuto	If you believe -- Early days -- College and beyond -- Milk and honey -- A damned exasperating woman -- Hello, Dolly! -- Mame -- Mame--and its movie -- Dear world -- Mack and Mabel -- The grand tour -- La cage aux folles -- After La cage -- The road ahead.
Sommario/riassunto	This revealing and comprehensive book tells the full story of Jerry Herman's life and career, from his early work in cabaret to his recent compositions for stage, screen, and television.Stephen Citron draws on extensive open-ended interviews with Jerry Herman as well as with scores of his theatrical colleagues, collaborators, and close friends. The resulting book-which sheds new light on each of Herman's musicals and their scores-abounds in fascinating anecdotes and behind-the-scenes details about the world of musical theater. Readers will find a sharply drawn portrait of Herman's private life and his creative talents. Citron's insights into Herman's music and lyrics, including voluminous examples from each of his musicals, are as instructive as they are edifying and entertaining.

2. Record Nr. UNINA9910830298803321

Titolo	Advanced plasma technology / / edited by Riccardo d'Agostino [and five others]
Pubbl/distr/stampa	Weinheim, Germany : , : Wiley-VCH Verlag GmbH & Co. KGaA, , 2008 ©2008
ISBN	1-281-94675-3 9786611946753 3-527-62218-7 3-527-62219-5
Descrizione fisica	1 online resource (481 p.)
Disciplina	621.044 660.004
Soggetti	Plasma engineering
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Description based upon print version of record.
Nota di bibliografia	Includes bibliographical references at the end of each chaptes and index.
Nota di contenuto	Advanced Plasma Technology; Contents; Preface; List of Contributors; 1 Basic Approaches to Plasma Production and Control; 1.1 Plasma Production; 1.1.1 Under Low Gas Pressure (10 torr); 1.2 Energy Control; 1.2.1 Electron-Temperature Control; 1.2.2 Ion-Energy Control; 1.3 Dust Collection and Removal; References; 2 Plasma Sources and Reactor Configurations; 2.1 Introduction; 2.2 Characteristics of ICP; 2.2.1 Principle; 2.2.2 Transformer Model; 2.2.3 Technological Aspects; 2.2.3.1 Matching 2.2.3.2 Capacitive Coupling2.2.3.3 Standing Wave Effects; 2.3 Sources and Reactor Configuration; 2.3.1 Substrate Shape; 2.3.1.1 Flat Substrates; 2.3.1.2 Complex Three-Dimensional Shapes; 2.3.1.3 Large Area Treatment; 2.4 Conclusions; References; 3 Advanced Simulations for Industrial Plasma Applications; 3.1 Introduction; 3.2 PIC Simulations; 3.2.1 Capacitively Coupled O(2)/Ar Plasmas; 3.2.1.1 Gas Composition; 3.2.1.2 Pressure Effect in Ar/O(2) Plasmas; 3.2.2 Three-Dimensional (3D) Charge-up Simulation; 3.2.2.1 Description of 3D Charge-up Simulations

3.2.2.2 Effects of Secondary Electron Emission3.2.2.3 Negative Ion Extraction; 3.3 Fluid Simulations; 3.3.1 Capacitively Coupled Discharges; 3.3.2 Large Area Plasma Source; 3.4 Summary; References; 4 Modeling and Diagnostics of He Discharges for Treatment of Polymers; 4.1 Introduction; 4.2 Experimental; 4.3 Model Description; 4.4 Results and Discussion; 4.4.1 Electrical Properties; 4.4.2 Gas-Phase Chemistry; 4.4.3 Plasma-Surface Interactions; 4.5 Conclusions; References; 5 Three-Dimensional Modeling of Thermal Plasmas (RF and Transferred Arc) for the Design of Sources and Industrial Processes 5.1 Introduction5.2 Inductively Coupled Plasma Torches; 5.2.1 Modeling Approach; 5.2.1.1 Modeling Assumptions; 5.2.1.2 Governing Equations of the Continuum Phase; 5.2.1.3 Governing Equations of the Discrete Phase; 5.2.1.4 Computational Domain and Boundary Conditions; 5.2.2 Selected Simulation Results; 5.2.2.1 High-Definition Numerical Simulation of Industrial ICPTs; 5.2.2.2 Numerical Simulation of the Trajectories and Thermal Histories of Powders Injected in Industrial ICPTs; 5.3 DC Transferred Arc Plasma Torches; 5.3.1 Modeling Approach; 5.3.1.1 Modeling Assumptions 5.3.1.2 Governing Equations5.3.1.3 Computational Domain and Boundary Conditions; 5.3.2 Selected Simulation Results; 5.3.2.1 Magnetically Deflected Transferred Arc; 5.3.2.2 The Twin Torch; 5.3.2.3 The Cutting Torch; References; 6 Radiofrequency Plasma Sources for Semiconductor Processing; 6.1 Introduction; 6.2 Capacitively Coupled Plasmas; 6.2.1 Dual-Frequency CCPs; 6.3 Inductively Coupled Plasmas; 6.3.1 General Description; 6.3.2 Anomalous Skin Depth; 6.3.3 Magnetized ICPs; 6.4 Helicon Wave Sources; 6.4.1 General Description; 6.4.2 Unusual Features; 6.4.3 Extended Helicon Sources; References 7 Advanced Plasma Diagnostics for Thin-Film Deposition

Sommario/riassunto

A panel of internationally renowned scientists discuss the latest results in plasma technology. This volume has been compiled with both a didactic approach and an overview of the newest achievements for industrial applications. It is divided into two main sections. One is focused on fundamental technology, including plasma production and control, high-pressure discharges, modeling and simulation, diagnostics, dust control, and etching. The section on application technology covers polymer treatments, silicon solar cell, coating and spray, biomaterials, sterilization and waste treatment, plasma